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Contents of previous two issues

May 1965

Vol. 9, No. 3

● *Articles:*

Fresnel Holograms: Their Imaging Properties and Aberrations
by *J. A. Armstrong*.....171

Analysis of the Impurity Atom Distribution Near the Diffusion Mask for a Planar p-n Junction
by *D. P. Kennedy and R. R. O'Brien*.....179

Some Numerical Experiments in the Theory of Polynomial Interpolation
by *F. W. Luttmann and T. J. Rivlin*.....187

● *Letter to the Editor:*

On a Circular Crack in a Transversely Isotropic Elastic Material Under Prescribed Shear Stress
by *W. T. Chen and R. P. Soni*.....192

● *Short Communications:*

Chain Matrices and the Crank-Nicolson Equation
by *H. P. Flatt*.....196

A Drive Scheme for the GaAs-Si Light-Activated Switch
by *P. Polgar, M. M. Roy and T. H. Yeh*.....200

Mapping an Arbitrary Range Into $(-1, 1)$ with a Side Condition: Application to Numerical Quadratures
by *A. D. McLean and M. Yoshimine*.....203

A New Technique for Dynamic Analysis of Acoustical Noise
by *R. H. Peterson and R. L. Hoffman*.....205

● *Communications Articles:*

- On Communications and Data Processing:
A Foreword
by *M. C. Andrews*.....226
- A New Approach to Time-Domain Equalization
by *E. Gorog*.....228
- Decoding of Cyclic Codes Using Position
Invariant Functions
by *J. D. Ullman*.....233
- A Comparison of Pseudo-Noise and Conventional
Modulation for Multiple-Access Satellite
Communications
by *H. Blasbalg*.....241
- A Pulsed Pseudo-Noise VHF Radio Set
by *F. Corr, R. Crutchfield and J. Marchese*.....256
- Analysis and Simulation of a Digital Matched
Filter Receiver of Pseudo-Noise Signals
by *R. Van Blerkom, R. E. Sears and D. G. Freeman*..264
- Design of an Automatic Telephone Intercept Switch
by *G. F. Abbott, R. L. Bence, J. A. Ceonzo
and J. M. Regan*.....274
- Filter Performance in Integrated Switching
and Multiplexing
by *K. M. Roehr, P. M. Thrasher
and D. J. McAuliffe, Jr.*.....282
- *Short Communication:*
- On Definitions of a Burst
by *R. T. Chien and D. T. Tang*.....292

● *Regular Articles:*

- A Technique for Determining and Coding Subclasses
in Pattern Recognition Problems
by *R. L. Mattson and J. E. Dammann*.....294
- Thermal Problems of the Injection Laser
by *R. W. Keyes*.....303
- Properties of GaAs Diodes with P-P⁰-N Structures
by *K. Weiser*.....315
- Vapor-Phase Polishing of Silicon
with H₂-HBr Gas Mixtures
by *L. V. Gregor, P. Balk, F. J. Campagna*.....327
- *Short Communications:*
- Two-Dimensional Laser Deflection
Using Fourier Optics
by *H. J. Zweig*.....333
- Fatigue Strength of Case Hardened Steel Specimens
Containing Through-The-Case Cracks
by *W. D. Kehr*.....336

Addendum to Volume 9, Number 4:

Figure 9b of the paper "Properties of GaAs Diodes with P-P⁰-N Structure" published in Volume 9, Number 4 (July 1965) of this Journal was obtained through the courtesy of T. English of the T. J. Watson Research Center who performed certain of the measurements cited in the paper. The author regrets that proper thanks and acknowledgement were not extended at the time of publication.

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